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Docket No. 0524-0140.01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:)
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Nozawa et al.)
)
Serial No.: 10/667,823)
)
Filed: September 22, 2003)
)
For: Phase Mask Shift Blank, Photo Mask Blank,)
And Manufacturing Apparatus And Method)
Of Blanks)
)
Examiner: Rodney Glenn McDonald)
)
)
Art Unit: 1753)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents , P.O. Box 1450, Alexandria, VA 22313-1450 on <u>January 23 2006</u> (Date of Deposit)	
<u>Shannon Wallace</u> Name of applicant, assignee, or Registered Rep.	
<u>Shannon Wallace</u> Signature	<u>1/23/06</u> Date

Commissioner of Patents
P. O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT (C) AFTER FINAL

Dear Sir:

In response to the Final Rejection of October 24, 2005, please enter the following amendment
in the above-identified application: